

Description

OPTICAL SYSTEM

CROSS REFERENCE TO RELATED APPLICATIONS

[0001] This application is a continuation of pending International Application PCT/EP02/08695, with an international filing date of August 05, 200²~~3~~._Λ

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BACKGROUND OF INVENTION

[0002] 1. Field of the Invention

[0003] The invention relates to an optical system and in particular to a projection exposure apparatus for microlithography. More particularly, the invention relates to a projection exposure apparatus with rotationally asymmetrical illumination, e.g. having a slot-shaped image field.

[0004] 2. Description of Related Art

[0005] An optical system of this kind is known from EP 0 823 662 A2. In that system, correction beams are directed through the projection objective parallel to the projection light. The correction radiation is absorbed by at least one opti-